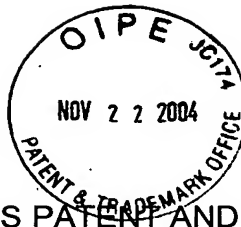


Docket Number: 081468-0310717
Client Reference: P-1943.063-US



PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of

HOFFMAN et al.

Group Art Unit: 2873

Application No.: 10/759,699

Examiner: M. HASAN

Filed: January 19, 2004

Confirmation No.: 8455

For: CORRECTION OF BIREFRINGENCE IN CUBIC CRYSTALLINE OPTICAL
SYSTEMS

November 22, 2004

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. One copy of each foreign reference and article is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom. Applicants respectfully request the Examiner return an initialed copy of the enclosed Form PTO-1449 to Applicants with the next Office communication to indicate that the reference(s) has been considered, per MPEP § 609.

This Information Disclosure Statement is being filed more than three months after the U.S. filing date AND after the mailing date of the first Office Action on the merits, but before the mailing date of a Final Rejection or Notice of Allowance.

English-language Abstracts of the non-English language references are attached hereto.

11/23/2004 FFANAEIA 00000103 033975 10759699


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HOFFMAN et al. — 10/759,699
Docket No. 081468-0310701

Please charge the \$180.00 fee for the filing of this Information Disclosure
Statement to Deposit Account No. 033975.

Respectfully submitted,

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Atty. Dkt. No.	M#	Client Ref.
	310701	P-1943.063-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: HOFFMAN et al.

Appln. No.: 10/759,699

Filing Date: January 19, 2004

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Examiner: M. HASAN Group Art Unit: 2873

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	UR	DE 101 27 320	12/2002	Germany	Brunotte et al.	X			
	VR	DE 102 10 782	10/2003	Germany	Krähmer et al.	X			
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	ZR								
	AAR								

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

BBR			
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FORM PTO-1449 (modified)
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Patent and Trademark Office

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Examiner: M. HASAN

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant: HOFFMAN et al.	
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